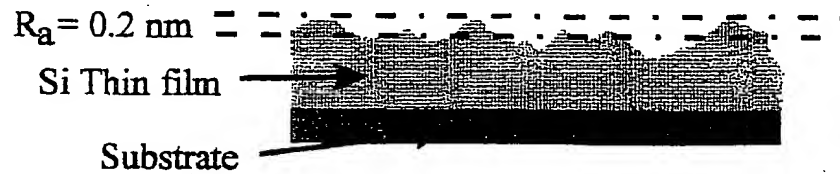
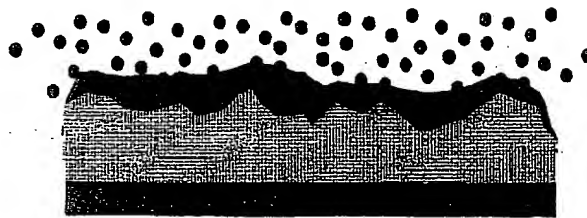


# SURFACE PLANARIZATION (Modified CRISP) PROCESS

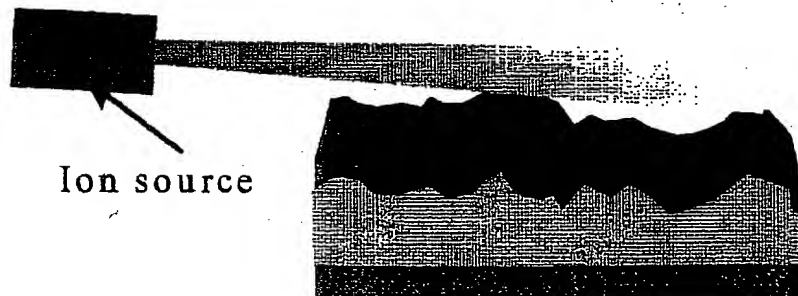
A) Atomic Layer Deposited Amorphous Si thin film



B) Amorphous Diamond-Like Carbon Deposition



C) Chemical etching of carbon by highly focused oxygen ion beam at near grazing incidence



D) Planarized surface with significantly reduced surface roughness

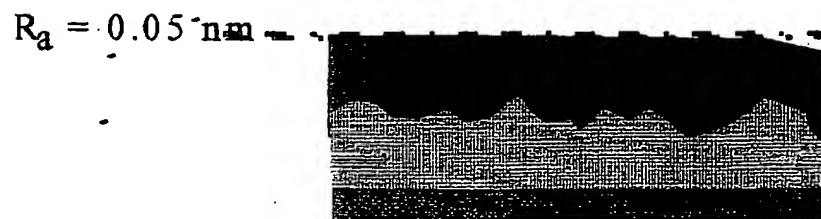


FIGURE 1